



Docket No.: M4065.0478/P478
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Glen Hush, et al.

Application No.: 09/988,627

Confirmation No.: 8791

Filed: November 20, 2001

Art Unit: 2824

For: COMPLEMENTARY BIT PCRAM SENSE
AMPLIFIER AND METHOD OF
OPERATION

Examiner: N. Nguyen

THIRD SUPPLEMENTAL
INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RECEIVED
SEP - 2 2003
TECHNOLOGY CENTER 2800

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached PTO/SB/08. It is respectfully requested that the subject matter of the documents be expressly considered during the prosecution of this application and that the documents be made of record therein and appear among the "References Cited" on any patent to issue from this application. A copy of each document is attached.

This Third Supplemental Information Disclosure Statement is being filed concurrently with a Request for Continued Examination.

A brief explanation of relevance of certain non-patent documents listed on Form PTO/SB/08 is provided and attached hereto as Appendix A. The brief explanation provided for each document is not tantamount to an admission that a document is "material" or that it qualifies as prior art. The Examiner is respectfully requested to utilize

Appendix A only as a tool by which to better categorize the documents for substantive use in examining the claims of the application.

Documents discussed in Appendix A marked with an asterisk (*) are indicated to be potentially more relevant than others. Such marking is provided only to assist the Examiner; however, the Examiner is requested to thoroughly review all documents cited herein.

In accordance with 37 C.F.R. § 1.97(g), the filing of this Supplemental Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 C.F.R. § 1.56(a) exists. It is submitted that this Supplemental Information Disclosure Statement is in compliance with 37 C.F.R. § 1.98 and the Examiner is respectfully requested to consider and cite the listed documents.

The Commissioner is authorized to charge any deficiency in the fees filed, asserted to be filed, or which should have been filed herewith (or with any paper hereafter filed in this application by this firm), to our Deposit Account No. 04-1073, under Order No. M4065.0478/P478.

Dated: August 27, 2003

Respectfully submitted,

By 

Thomas J. D'Amico
Registration No. 28,371
Salvatore P. Tamburo
Registration No. 45,153
DICKSTEIN SHAPIRO MORIN &
OSHINSKY LLP
2101 L Street, N.W.
Washington, DC 20037-1526
(202) 785-9700

Attorneys for Applicants

APPENDIX A

Japanese patent application publication No. 56126916A by Akira: this published application generally relates to, inter alia, diffusing selenium with high accuracy into a chalcogenide with silver by use of photoresist and thermal treatment.

*Axon Technologies Corp., *Technology Description: Programmable Metallization Cell*: this believed publication generally relates to, inter alia, use of chalcogenides doped with metal much as silver or copper to create solid state switch with lower voltage requirement.

Helbert et al., SPIE Vol. 333 Submicron Lithography (1982): this publication generally relates to, inter alia, hybrid ultragraphic process using both electron beam and conventional optical exposure within the same device level with a photoresist.

Hilt, dissertation (1999): this publication generally relates to, inter alia, stability of chalcogenides such as $\text{Ge}_x\text{Se}_{1-x}$ with Ag doping by photodissolution and thermal diffusion.

Hirose et al., Phys. Stat. Sol. (1980): this publication generally relates to, inter alia, switch and memory phenomena in amorphous As_2S_3 with photo-doped Ag, including new mechanism, electrical reliability, rapid memory performance, thermal characteristics and durability

Holmquist et al., 62 J. Amer. Ceram. Soc., No. 3-4 (March-April 1979): this publication generally relates to, inter alia, reactions and diffusion of Ag in arsenic chalcogenide glass below the glass transition temperature, including solubility information and concentration dependence of Ag diffusion in these glasses.

Huggett et al., 42 Appl. Phys. Lett., No. 7 (April 1983): this publication generally relates to, inter alia, reactive sputter etching to develop silver-sensitized $\text{Ge}_x\text{Se}_{1-x}$ photoresist.

Kawaguchi et al., 164-166 J. Non-Cryst. Solids (1993): this publication generally relates to, inter alia, deposition mechanism of Ag particles on Ag-rich Ag-As-S glass from a view-point of electrical effects.

*Kolobov and Elliott, Advances in Physics (1991): this publication generally relates to, inter alia, photodoping (photodiffusion/photodissolution) of amorphous chalcogenides by metals, particularly silver.

*Kozicki et al., Superlattices and Microstructures, 27 (2000): this publication generally relates to, inter alia, solid solutions of metals (e.g., silver) in arsenic trisulfide and their physical and electrical characteristics.

*Kozicki et al., Microelectronic Engineering, vol. 63/1-3 (2002): this publication generally relates to, inter alia, the photodiffusion of Ag into germanium selenide glass films, the amount of Ag that can be incorporated in to such a film by photodiffusion, and the characteristics of the resulting doped films.

*Kozicki et al., Proceedings of the 1999 Symposium on Solid State Ionic Devices (1999): this publication generally relates to, inter alia, physical and electrical characteristics of metal doped chalcogenide films (photodoped $\text{Ag}_4\text{As}_2\text{S}_3$) between electrodes, useful in memories, configurable connections, and self-repairing interconnections.

*Kozicki and Mitkova, Proceedings of the XIX International Congress on Glass, Society for Glass Technology (2001): this publication generally relates to, inter alia, the physical effects of introduction of Ag into chalcogenide glasses, where introduction is by photodiffusion.

McHardy et al., 20 J. Phys. C.: Solid State Phys. (1987): this publication generally relates to, inter alia, sensitivity and high resolution of metals in amorphous chalcogenides by electron and UV radiation.

Owen et al., Nanostructure Physics and Fabrication (1989): this publication generally relates to, inter alia, photo-induced structural or physico-chemical changes of amorphous chalcogenides when exposed to light/irradiation, affecting chemical solubility.

Shimizu et al., 46 B. Chem Soc. Japan, No. 12 (1973): this publication generally relates to, inter alia, electric conductivity increase by increasing Ag-photodoping of chalcogenide glass.



PTO/SB/08A (10-01)

Approved for use through 10/31/2002.OMB 0651-0031

U. S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Complete if Known	
				Application Number	09/988,627
				Filing Date	November 20, 2001
				First Named Inventor	Glen Hush
				Art Unit	2824
				Examiner Name	N. Nguyen
Sheet	1	of	3	Attorney Docket Number	M4065.0478/P478

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
	AA	2000/0072188 App	6/2002	Gilton	
	AB	2002/0106849 APP	8/8/2002	Moore	
	AC	2002/0123169 App	9/2002	Moore et al.	
	AD	2002/0123170 APP	9/5/2002	Moore et al.	
	AE	2002/0123248 App.	9/2002	Moore et al.	
	AF	2002/0127886 APP	9/12/2002	Moore et al.	
	AG	2002/0163828 APP	11/2002	Krieger et al	
	AH	2002/0168820 App.	11/2002	Kozicki	
	AI	2002/0190350 APP	12/19/2002	Kozicki	
	AJ	2003/0001229 APP	1/2/2003	Moore et al.	
	AK	2003/0027416 APP	2/6/2003	Moore	
	AL	2003/0035314	02/20/03	Kozicki	
	AM	2003/0035315	02/20/03	Kozicki	
	AN	2003/0107105 A1	06/12/03	Kozicki	
	AO	3,622,319	11/1971	Sharp	
	AP	3,743,847	7/1973	Boland	
	AQ	4,112,512	9/5/1978	Arzubi et al.	
	AR	4,269,935	5/1981	Masters et al.	
	AS	4,312,938	1/1982	Drexler, et al.	
	AT	4,316,946	1/1982	Masters, et al.	
	AU	4,320,191	3/1982	Yoshikawa et al.	
	AV	4,405,710	9/1983	Balasubramanyam et al.	
	AW	4,419,421	12/1983	Wichelhaus, et al.	
	AX	4,499,557	2/1985	Holmberg et al.	
	AY	4,671,618	6/87	Wu et al.	
	AA1	4,795,657	1/1989	Formigoni et al.	
	AB1	4,800,526	1/89	Lewis	
	AC1	4,847,674	7/1989	Sliwa et al.	
	AD1	5,177,567	1/1993	Klersy et al.	
	AE1	5,219,788	6/1993	Abernathay et al.	
	AF1	5,238,862	8/1993	Blalock et al.	
	AG1	5,272,359	12/93	Nagasubramanian et al.	
	AH1	5,314,772	5/24/1994	Kozicki	
	AI1	5,315,131	5/1994	Kishimoto et al.	
	AJ1	5,350,484	9/1994	Gardner et al.	
	AK1	5,360,981	11/1994	Owen et al.	
	AL1	5,512,328	4/1996	Yoshimura et al.	
	AM1	5,512,773	4/1996	Wolf et al.	
	AN1	5,699,293	12/16/1997	Tehrani et al.	
	AO1	5,726,083	3/1998	Takaishi	
	AP1	5,818,749	10/6/98	Harshfield	
	AQ1	5,841,150	11/1998	Gonzalez et al.	
	AR1	5,846,889	12/1998	Harbison et al.	
	AS1	5,883,827	3/16/1999	Morgan	
	AT1	5,920,788	7/1999	Reinberg	



PTO/SB/08A (10-01)

Approved for use through 10/31/2002.OMB 0651-0031

U. S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Complete if Known	
				Application Number	09/988,627
				Filing Date	November 20, 2001
				First Named Inventor	Glen Hush
				Art Unit	2824
				Examiner Name	N. Nguyen
Sheet	2	of	3	Attorney Docket Number	M4065.0478/P478

	AU1	5,998,066	12/1999	Block et al.	
	AV1	6,072,716	6/2000	Jacobson et al.	
	AW1	6,077,729	6/2000	Harshfield	
	AX1	6,117,720	9/2000	Harshfield	
	AY1	6,143,604	11/2000	Chiang et al.	
	AZ1	6,177,338	1/2001	Liaw et al.	
	BA1	6,191,972	2/20/2001	Miura et al.	
	BB1	6,191,989	2/20/2001	Luk et al.	
	BC1	6,236,059	5/2001	Wolstenholme et al.	
	BD1	6,243,311	6/5/2001	Keeth	
	BE1	6,297,170	10/2001	Gabriel et al.	
	BF1	6,300,684	10/2001	Gonzalez et al.	
	BG1	6,316,784	11/2001	Zahorik et al.	
	BH1	6,329,606	12/2001	Freyman et al.	
	BI1	6,350,679	2/2002	McDaniel et al.	
	BJ1	6,376,284	4/2002	Gonzalez et al.	
	BL1	6,391,688	5/2002	Gonzalez et al.	
	BM1	6,414,376	7/2002	Thakur et al.	
	BN1	6,423,628	7/2002	Li et al.	
	BO1	6,462,981	10/08/2002	Numata et al.	
	BP1	6,469,364	10/2002	Kozicki	
	BQ1	6,473,332	04/04/01	Ignatiev et al.	
	BR1	6,487,106	11/26/2002	Kozicki	

FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)			
	BA	56126916	10/19981	Akira et al.	
	BB	EP 1 109 170 A2	6/20/2001	Kabushiki Kaisha Toshiba	
Examiner Signature				Date Considered	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant

¹ Applicant's unique citation designation number (optional). ² See attached Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the application number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449B/PTO				<i>C mplete if Kn wn</i>	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>				Application Number	09/988,627
				Filing Date	November 20, 2001
				First Named Inventor	Glen Hush
				Group Art Unit	2824
				Examiner Name	N. Nguyen
				Attorney Docket Number	M4065.0483/P483
Sheet	3	of	3		

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	CA	Axon Technologies Corporation, TECHNOLOGY DESCRIPTION: <i>Programmable Metalization Cell(PMC)</i> , pp. 1-6 (Pre-May 2000).	
	CB	Helbert et al., <i>Intralevel hybrid resist process with submicron capability</i> , SPIE Vol. 333 SUBMICRON LITHOGRAPHY, pp. 24-29 (1982).	
	CC	Hill, DISSERTATION: <i>Materials characterization of Silver Chalcogenide Programmable Metalization Cells</i> , Arizona State University, pp. Title page-114 (UMI Company, May 1999).	
	CD	Hirose et al., <i>High Speed Memory Behavior and Reliability of an Amorphous As₂S₃ Film Doped Ag</i> , PHYS. STAT. SOL. (a) 61, pp. 87-90 (1980).	
	CE	Holmquist et al., <i>Reaction and Diffusion in Silver-Arsenic Chalcogenide Glass Systems</i> , 62 J. AMER. CERAM. SOC., No. 3-4, pp. 183-188 (March-April 1979).	
	CF	Huggett et al., <i>Development of silver sensitized germanium selenide photoresist by reactive sputter etching in SF₆</i> , 42 APPL. PHYS. LETT., No. 7, pp. 592-594 (April 1983).	
	CG	Kawaguchi et al., <i>Mechanism of photosurface deposition</i> , 164-166 J. NON-CRYST. SOLIDS, pp. 1231-1234 (1993).	
	CH	Kolobov and Elliott, Photodoping of Amorphous Chalcogenides by Metals, Advances in Physics, Vol. 40, No 5, 625-684 (1991).	
	CI	Kozicki, et al., "Applications of Programmable Resistance Changes in Metal-doped Chalcogenides", Proceedings of the 1999 Symposium on Solid State Ionic Devices, Editors - E.D. Wachsman et al., The Electrochemical Society, Inc., 1 - 12 (1999).	
	CJ	Kozicki, et al., <i>Nanoscale effects in devices based on chalcogenide solid solutions</i> , Superlattices and Microstructures, 27, 485-488 (2000).	
	CK	Kozicki, et al., <i>Nanoscale phase separation in Ag-Ge-Se glasses</i> , Microelectronic Engineering, vol. 63/1-3, 155-159 (2002).	
	CL	M.N. Kozicki and M. Mitkova, <i>Silver incorporation in thin films of selenium rich Ge-Se glasses</i> , Proceedings of the XIX International Congress on Glass, Society for Glass Technology, 226-227 (2001).	
	CM	McHardy et al., <i>The dissolution of metals in amorphous chalcogenides and the effects of electron and ultraviolet radiation</i> , 20 J. PHYS. C.: SOLID STATE PHYS., pp. 4055-4075 (1987)f	
	CN	Owen et al., <i>Metal-Chalcogenide Photoresists for High Resolution Lithography and Sub-Micron Structures</i> , NANOSTRUCTURE PHYSICS AND FABRICATION, pp. 447-451 (M. Reed ed. 1989).	
	CO	Shimizu et al., <i>The Photo-Erasable Memory Switching Effect of Ag Photo-Doped Chalcogenide Glasses</i> , 46 B. CHEM SOC. JAPAN, No. 12, pp. 3662-3365 (1973).	
	CP	Scheuerlein R. et al., <i>A 10ns Read and Write Non-Volatile Memory Array Using a Magnetic Tunnel Junction and FET Switch in each Cell</i> , Digest of Technical Papers. 2000 IEEE Int'l Solid-State Circuits Conference, Session 7, Paper TA 7.2, 8 February 2000, pages 128-129.	

SEP-2 2000
 TECHNOLOGY CENT
 RECEIVED

Examiner Signature		Date Considered	
--------------------	--	-----------------	--

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Applicant's unique citation designation number (optional). ²Applicant is to place a check mark here if English language Translation is attached.